What is claimed is:

- 1. Monoazo metal complex compound containing composition, the incidence of skin sensitization in a skin sensitization potential test of said composition being not more than 20%.
- 2. Monoazo metal complex compound containing composition of Claim 1 wherein said skin sensitization potential test is a skin sensitization potential test based on the maximization method.
- 3. Monoazo metal complex compound containing composition of Claim 1 wherein the purity of said monoazo metal complex compound is not less than 90% as determined by high performance liquid chromatography.
- 4. Monoazo metal complex compound containing composition of Claim 2 wherein the purity of said monoazo metal complex compound is not less than 90% as determined by high performance liquid chromatography.
- 5. Monoazo metal complex compound containing composition of any of Claims 1, 2, 3 or 4 wherein said monoazo metal complex compound is a compound of the following formula (1):

wherein each of R¹ through R⁴ and R⁶ independently represents a hydrogen atom, a normal or branched alkyl group having 1 to 18 carbon atoms, a normal

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or branched alkenyl group having 2 to 18 carbon atoms, a sulfonamide group, a mesyl group, a sulfonic acid group, a hydroxy group, an alkoxy group having 1 to 18 carbon atoms, an acetylamino group, a benzoylamino group, a halogen atom, or -COO-R⁷;

R⁷ represents a normal or branched alkyl group having 1 to 18 carbon atoms or an aryl group having 6 to 18 carbon atoms;

R⁵ represents a hydrogen atom, a halogen atom, a nitro group, a carboxyl group, a normal or branched alkyl group having 1 to 18 carbon atoms, an alkenyl group having 2 to 18 carbon atoms, an alkoxy group having 1 to 18 carbon atoms, an aryl group having 6 to 18 carbon atoms, -COO-R⁸ or

R⁸ represents a normal or branched alkyl group having 1 to 18 carbon atoms or an aryl group having 6 to 18 carbon atoms;

Y represents a hydrogen atom, a normal or branched alkyl group having 1 to 8 carbon atoms, an alkoxy group having 1 to 5 darbon atoms, a nitro group, or a halogen atom;

m represents an integer from 1 to 3;

M represents a divalent or trivalent metal;

p represents 1 or 2;

(A)^{q+} represents H⁺, NH₄⁺, a cation based on an alkali metal, a cation based on an organic amine, or a quaternary organic ammonium ion;

q represents 1 or 2; and

X represents 1 or 2.

6. Monoazo metal complex compound containing composition of Claim 5

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wherein R² in Formula (1) above is Cl;

each of R¹ and R³ through R⁵ is\a hydrogen atom;

R⁶ is a hydrogen atom or a normal or branched alkyl group having 1 to 18 carbon atoms;

- M is Cr, Fe, or Cu; and $(A)^{q+}$ is H^{+} .
 - 7. Method for producing a monoazo metal complex compound containing composition which comprises a step for removing impurity substances using an alcoholic organic solvent, the incidence of skin sensitization in a skin sensitization potential test of said composition being not more than 20%.
 - 8. Method for producing the monoazo metal complex compound containing composition of Claim 7 wherein said skin sensitization potential test is a skin sensitization potential test based on the maximization method.
 - 9. Method for producing the monoazo metal complex compound containing composition of Claim 7 wherein the purity of said monoazo metal complex compound is not less than 90% as determined by high performance liquid chromatography.
 - 10. Method for producing the monoazo metal complex compound containing composition of Claim 8 wherein the purity of said monoazo metal complex compound is not less than 90% as determined by high performance liquid chromatography.
 - 11. Method for producing the monoazo metal complex compound containing composition of Claim 7, 8, 9 or 10 wherein said alcoholic organic solvent is one member or a mixture of two or more members selected from the group consisting of methanol, ethanol, 1-propanol, 2-propanol, n-butanol,

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ethylene glycol, propylene glycol monomethyl ether and ethylene glycol monoethyl ether.

- 12. Method for producing a monoazo metal complex compound containing composition which comprises a step for synthesizing a monoazo metal complex compound in an alcoholic organic solvent, and a step for removing impurity substances from the product of the synthetic step using an alcoholic organic solvent, the incidence of skin sensitization in a skin sensitization potential test of said composition being not more than 20%.
- 13. Method for producing the monoazo metal complex compound containing composition of Claims 12 wherein said skin sensitization potential test is a skin sensitization potential test based on the maximization method.
- 14. Method for producing the monoazo metal complex compound containing composition of Claims 12 wherein the purity of said monoazo metal complex compound is not less than 90% as determined by high performance liquid chromatography.
- 15. Method for producing the monoazo metal complex compound containing composition of Claims 13 wherein the purity of said monoazo metal complex compound is not less than 90% as determined by high performance liquid chromatography.
- 16. Method for producing the monoazo metal complex compound containing composition of Claim 12, 13, 14 or 15 wherein said alcoholic organic solvent is one member or a mixture of two or more members selected from the group consisting of methanol, ethanol, 1-propanol, 2-propanol, n-butanol, ethylene glycol, propylene glycol monomethyl ether and ethylene glycol monoethyl ether.

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- 17. Method for producing a monoazo metal complex compound containing composition which comprises a step for synthesizing a monoazo metal complex compound in an alcoholic organic solvent, and a step for removing impurity substances by directly filtering a reaction mixture containing the product obtained by the synthetic step, the incidence of skin sensitization in a skin sensitization potential test of said composition being not more than 20%.
- 18. Method for producing the monoazo metal complex compound containing composition of Claims 17 wherein said skin sensitization potential test is a skin sensitization potential test based on the maximization method.
- 19. Method for producing the monoazo metal complex compound containing composition of Claims 18 wherein the purity of said monoazo metal complex compound is not less than 90% as determined by high performance liquid chromatography.
- 20. Method for producing the monoazo metal complex compound containing composition of Claims 19 wherein the purity of said monoazo metal complex compound is not less than 90% as determined by high performance liquid chromatography.
- 21. Method for producing the monoazo metal complex compound containing composition of Claim 17, 18, 19 or 20 wherein said alcoholic organic solvent is one member or a mixture of two or more members selected from the group consisting of methanol, ethanol, 1-propanol, 2-propanol, n-butanol, ethylene glycol, propylene glycol monomethyl ether and ethylene glycol monoethyl ether.
- 22. Charge control agent comprising a monoazo metal complex compound
 25 containing composition, the incidence of skin sensitization in a skin

sensitization potential test of said composition being not more than 20%.

- 23. Toner for developing electrostatic images which contains a charge control agent comprising a monoazo metal complex compound containing composition, the incidence of skin sensitization in a skin sensitization potential test of said composition being not more than 20%.
- 24. Coloring agent containing the monoazo metal complex compound containing composition, the incidence of skin sensitization in a skin sensitization potential test of said composition being not more than 20%.
- 25. Colored thermoplastic resin composition containing the monoazo metal complex compound containing composition as a coloring agent, the incidence of skin sensitization in a skin sensitization potential test of said composition being not more than 20%.

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